# The FE-I4 Pixel Readout IC

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### FE-I4 Design Collaboration

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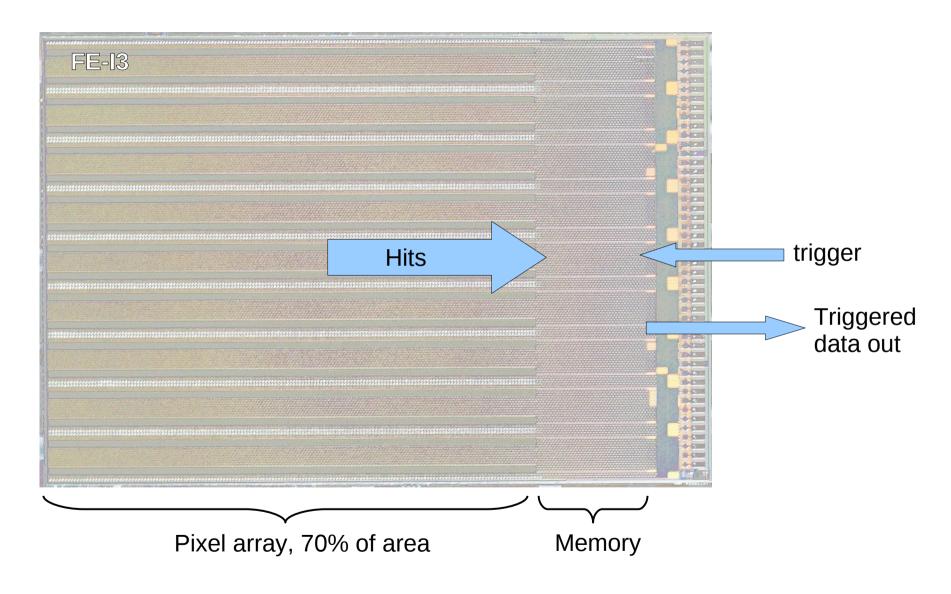
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Physicist/Students (specification, testing, etc)

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Designers collaborate remotely using the Cliosoft collaboration platform.

## Today's ATLAS pixel chip

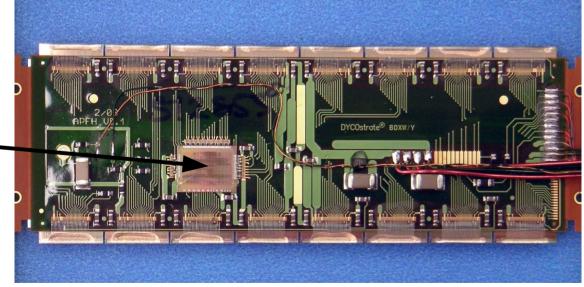


# Today's ATLAS module

16 chips on 1 sensor to cover a ~10cm² area



Digital module control chip



#### What would be better?

(a.k.a. FE-I4 specs)

- Much cheaper module manufacture (=> chip size as big as possible)
- Greater fraction of the footprint devoted to pixel array (=> move the memory inside the array)
- Lower power
   (=> don't move the hits around unless they are triggered)
- Able to take higher hit rate
   (=> store the hits locally and distribute the trigger)
- Still able to resolve the hits at higher rate
   (=> smaller pixels and faster recovery time)
- No need for extra control chip (=> significant digital logic blocks on array periphery)

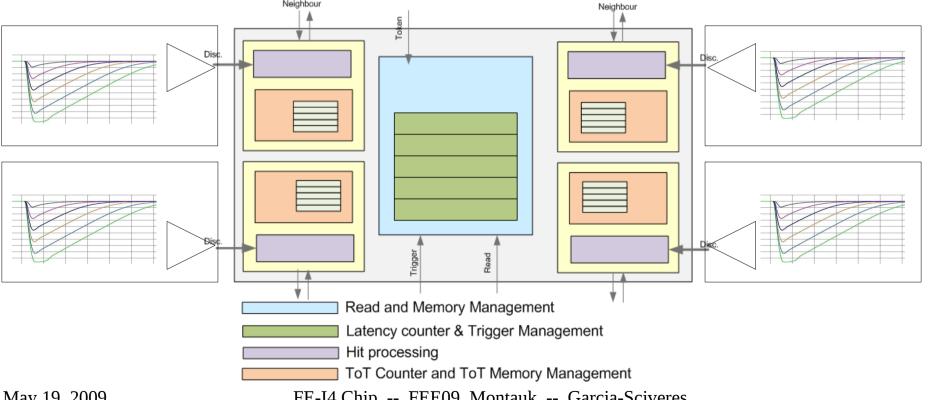
Region architecture

#### FE-I4 Pixel

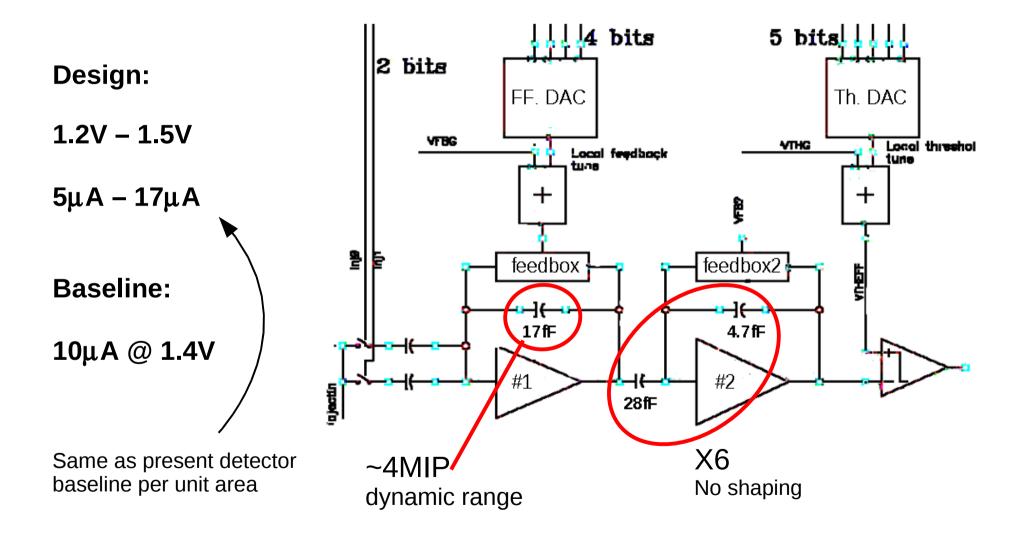
- Basic problem is how to reduce the pixel size and at the same time move memory and trigger processing into the pixel
- Move from 250nm CMOS6RF to 130nm CMOS8RF.
- Use linear transistors instead of enclosed layout
  - Any "analog" NMOS (i.e. one that is not a switch) is placed inside a guard ring, but geometry is still linear.
- Digital circuitry (hit memory and logic) in pixel is all synthesized standard cells.
- Is this enough? No
- The final improvement is to group the pixels into units called regions where the trigger processing is shared.
- This helps because hits from charged particles are naturally clustered.
  - If hits were random, with no spatial correlation, it would be less useful

### Region

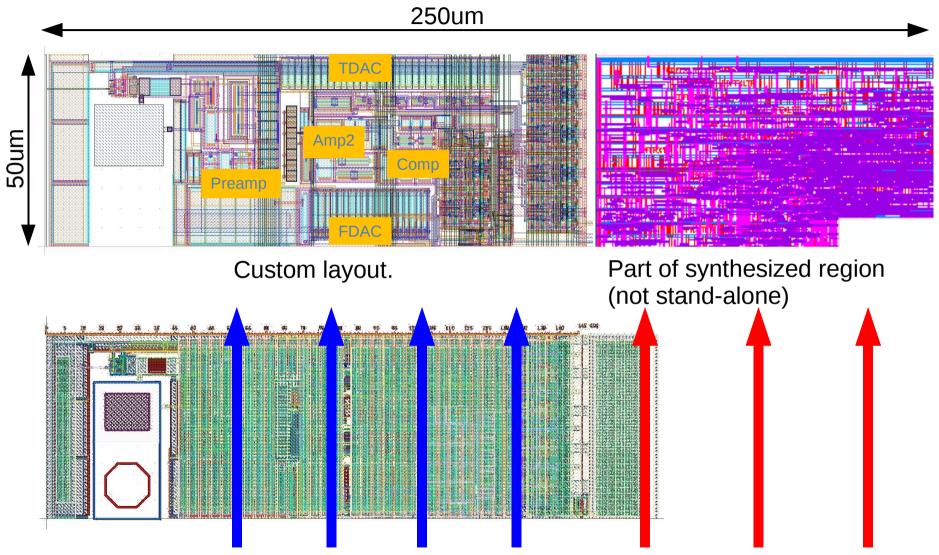
- 4 analog pixels, each ending with a comparator output (ADC function).
- One common digital region synthesized as one block.
- 5-deep TOT value memory for each pixel, but shared trigger latency counters.
- If 1 pixel is hit, 1 counter starts. If 2,3,4 pixels are hit, also only 1 counter starts.
- No region dead time (pixel A hit this crossing and B hit next crossing is OK)



### **Analog pixel**



### FE-I4 Pixel Layout

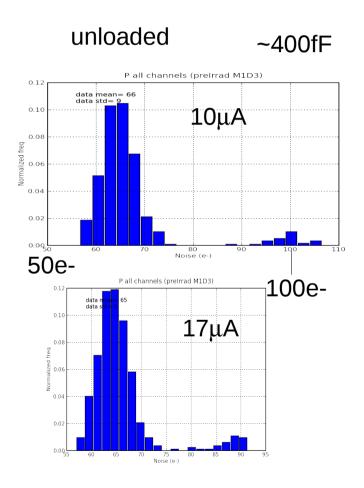


Power distribution and shield on top metals. Only vertical - no analog/digital crossing

#### Noise Performance

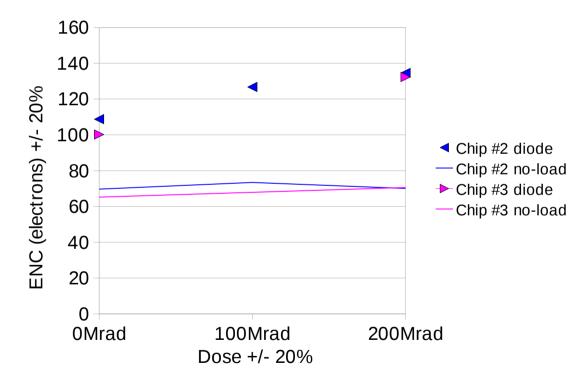
(measured in pixel array test chip)



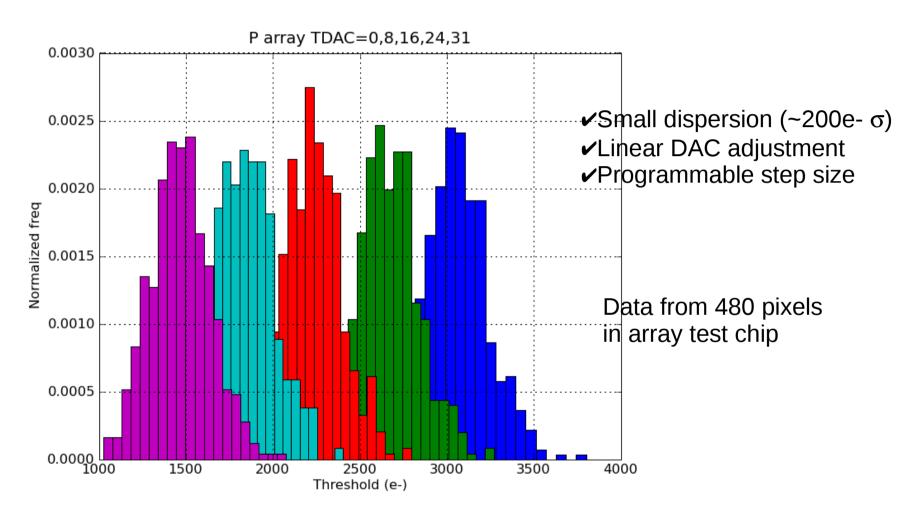


#### Irradiation:

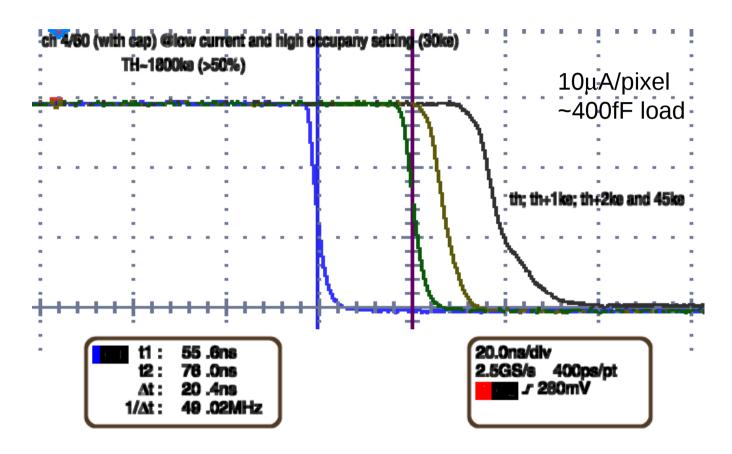
Loaded channels increased ~20%, But load is a diode! The load itself changes with radiation No bump-bonded assemblies yet.



#### **Threshold**



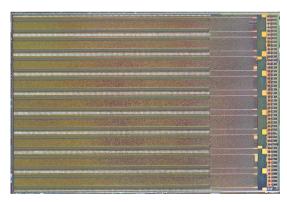
#### Time-walk



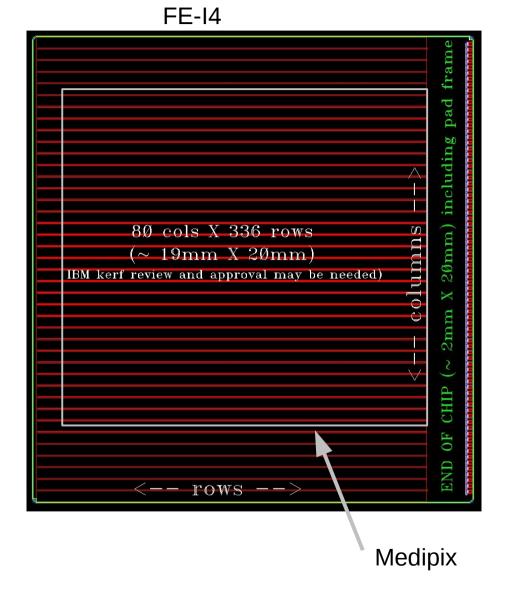
- Can be reduced by increasing analog current
- But there is no need (see later)

#### Die footprints to same scale

Analog pixel array demonstrator
Fabricated in 2008
Validation of analog performance
and radiation tolerance
(also digital circuit, LVDS, LDO, DC-DC, bias generator, etc.)



FE-I3 (present detector)



### FAQ

- Won't such a big chip have zero yield?
- What, you're placing synthesized standard cells next to sensitive amplifiers?!
- Why isn't lower analog performance due to reduced current an issue?
- What will be the minimum threshold for stable operation?
  - Sorry, we are not able to make a quantitative prediction for this.

### Yield hardening

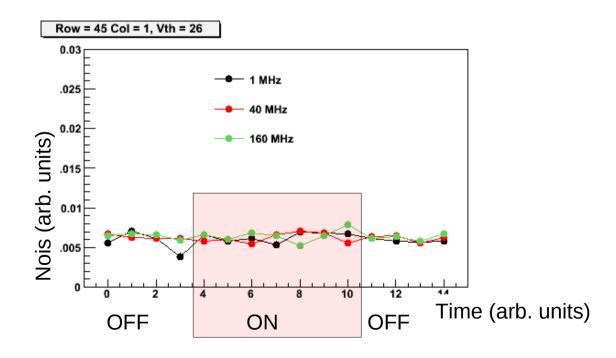
- Critical point: a physics grade pixel chip is NOT a perfect chip.
  - A certain fraction of dead pixels is acceptable
  - For present detector that was 5/2880 at wafer probing
  - "Vulnerable" area of chips << footprint</li>
- Nevertheless, for such a large chip we are combining 2 yield hardening approaches
  - Make probing "part of Fab" (for pixel config. SR & decoder)
    - Use e-fuses to select between 2 SR's at probing
  - Use standard defect tolerant methods requiring no user action
    - All region outputs Hamming coded
    - Read token triple redundant
    - Note SEU not an issue for internal data buses. Do not need to "preserve" redundancy for operation.
- Hope to use Medipix 3 wafer probe results to create a yield model for FE-I4

#### Substrate Coupling

- Standard cells hard-wire substrate to digital G.
  - Bad for sensitive analog circuits on same substrate.
- But nevertheless would like to take advantage of "canned" digital design flow.
- In this era of system-on-a-chip, we can't be the only ones with this problem!
- Plan to use new feature offered in CMOS8RF called T3 isolation
  - Basically a big N-well ( $100\mu m\ x$  anything) where a synthesized block can be placed.
  - Seems tailored to "our" particular problem.
  - Very small effect on circuit area.

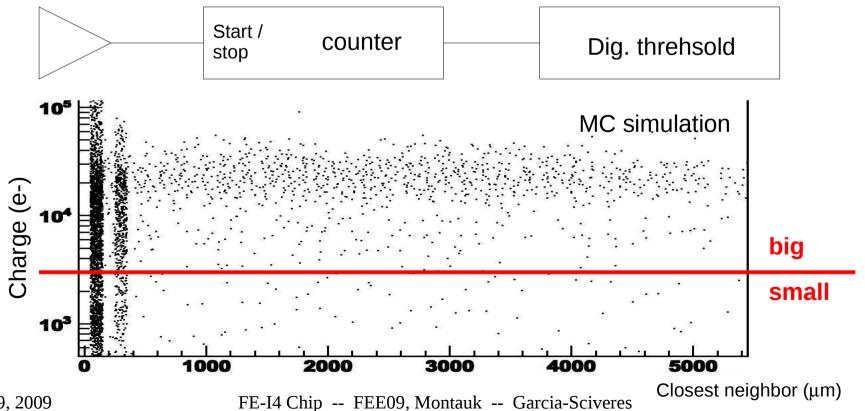
### Substrate coupling tests

- Have tried to noise coupling from a synthesized standard cell block to analog pixels in 2008 array test chip
  - No isolation was used here
- This does not prove anything, but suggests potential substrate coupling may not be very large.



#### Hit association

- Recall claim "higher current to improve time-walk not needed"
- Because we use a digital threshold with association of "small hits" by proximity, not time.
  - Large hits are in time
  - Small hits are close to large hits



### Other chip features prototyped and tested

- SEU registers- custom layout
- Shunt-LDO regulators for power conditioning and/or serial power implementation
- X2 Charge pump DC-DC converter
- Clock multiplier for up to 320Mb/s output from 40MHz input clock.
- LVDS compatible I/O
- Scan chains for testing digital circuitry
- Total dose (to 200MRad) and SEU radiation testing
- Detailed simulations of digital power consumption in array
  - (<10uA /pixel @ 1.2V)</li>

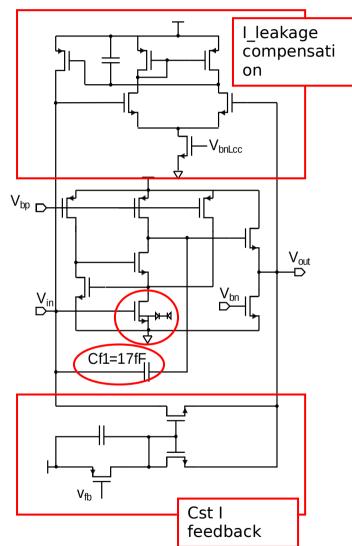
#### Conclusions

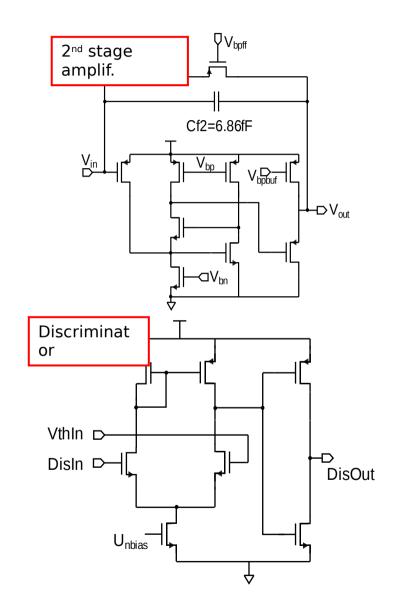
- FE-I4 blocks are technology choices defined.
- Will be the largest HEP pixel chip to date
  - Large reduction of module assembly cost
  - Expect yield of physics grade chips to be reasonable,
  - But additionally yield hardening the design of most blocks.
- Basic performance validated with small prototypes.
- Integration of a full size chip started
  - Submission planned this Fall (date not yet fixed)
- Will use synthesized standard cell layouts for all digital elements, with T3 isolation to keep substrate clean
- Distributed design collaboration approach is working very well.

# **BACKUP**

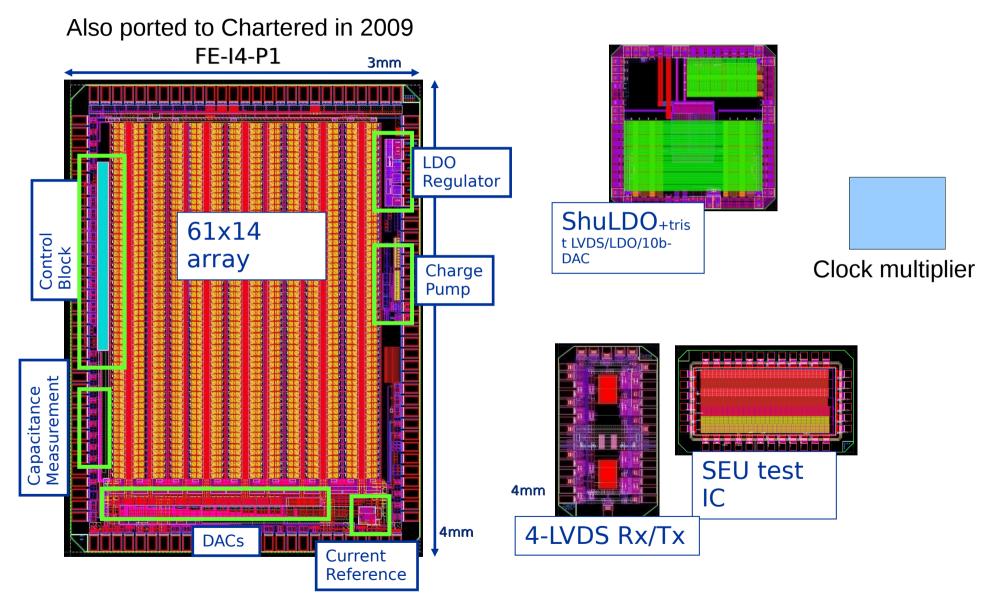
# Analog pixel



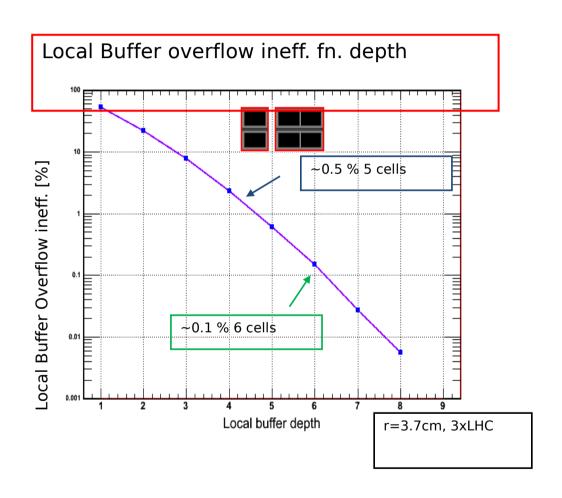




#### FE-I4 test chips



### Functional simulations (example)



### Digital power

Average for 4-pixel region. IBL occupancy

Simulation type	Power (avg) [uW]	
ETS	42.28	
Spectre <sup>2</sup>	25.19	
Ultarasim(s) <sup>2</sup>	24.69	
Ultarasim(a) <sup>2</sup>	24.73	@1.2V
Ultarasim(ms) <sup>2</sup>	35.12	
HSIM <sup>1</sup>	27.64	
HSIM <sup>2</sup>	30.98	

Parasitic extraction done width ¹PEX

Digital column pair layout (30K transistors shown) 300um slice